DOCKET NO.: 219625US99DIV

#2 PRIAMOH. A 7-1-02 Restutes

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

: EXAMINER

JAMAL RAMDANI

SERIAL NO.: NEW DIVISIONAL APPL.

FILED: HEREWITH

: GROUP ART UNIT

FOR: SEMICONDUCTOR STRUCTURE, SEMICONDUCTOR DEVICE,

COMMUNICATING DEVICE, INTEGRATED CIRCUIT, AND PROCESS

FOR FABRICATING THE SAME

PRELIMINARY AMENDMENT

Sir:

Prior to examination on the merits, please enter the following Amendment.

IN THE CLAIMS

Please cancel Claims 1-143.

Please add new Claims 144-237.

--144. A semiconductor structure comprising:

a plurality of material layers including:

a monocrystalline silicon substrate;

a monocrystalline perovskite oxide material overlying at least a portion of the monocrystalline silicon substrate;

an amorphous oxide material located between the monocrystalline perovskite oxide material and the monocrystalline silicon substrate;

a monocrystalline compound semiconductor material overlying at least a portion of the monocrystalline perovskite oxide material; and

A